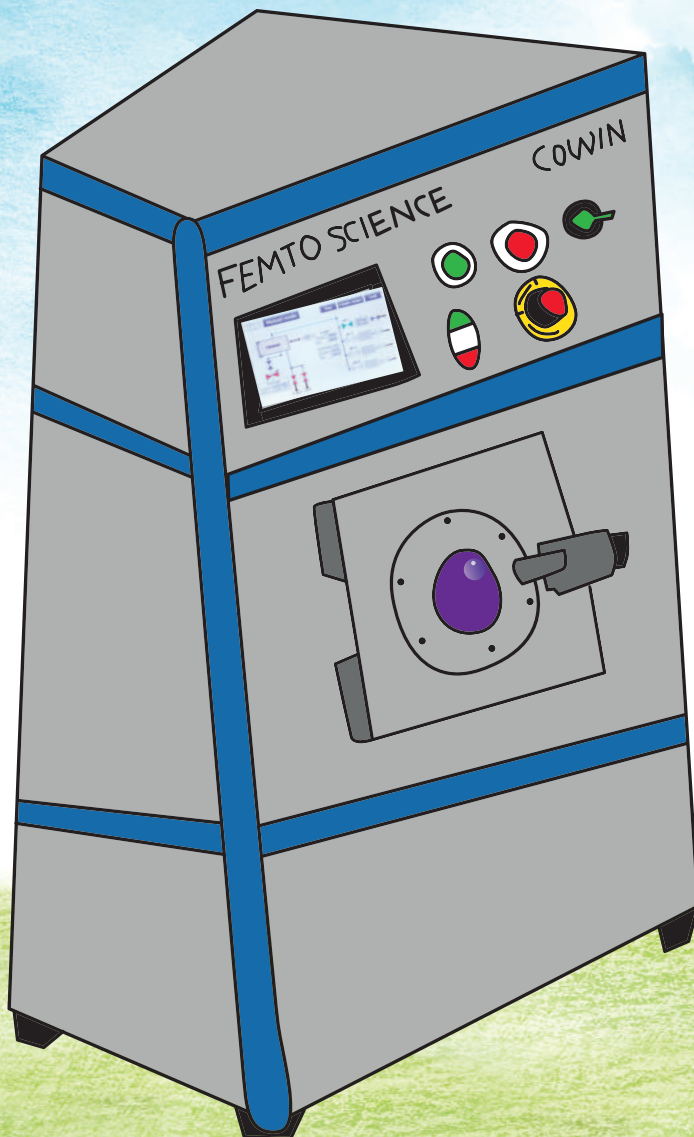


Plasma Processing System

COWIN-40





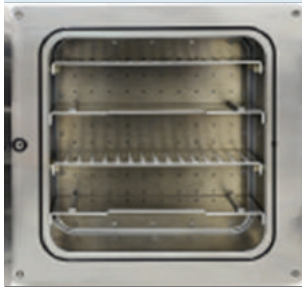
Specification

Model	COWIN-40
Process Mode	PE MODE
Chamber	W.330 x D.350 x H.340 (mm)
MFC	Max. 500 sccm
Gauge Pressure	Atm ~ 5×10^{-4} Torr
Operation	Manual & Automatic
Geometry	W.800 x D.800 x H.1800 (mm)

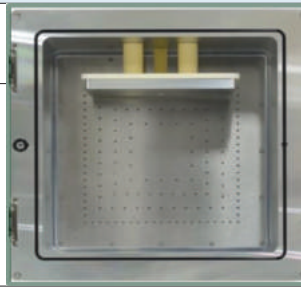
Generator

LF Generator	RF Generator
20~100kHz / Max. 300W	13.56MHz / Max. 300W

Electrode Assembly

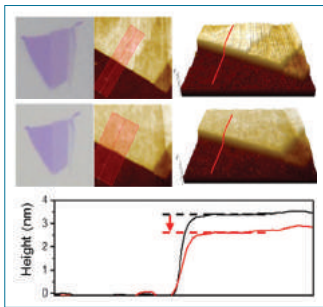


- Single electrode
 - Multi Electrode
- All electrodes are designed with the same impedance, with constant voltage and current values applied reliably. An independent discharge occurs for each electrode.

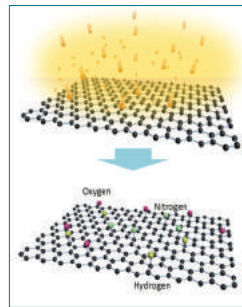


- Water Cooling Electrode
- Liquid cooling design
 - Top ceramic insulation pocket
 - RF noise shielding cover

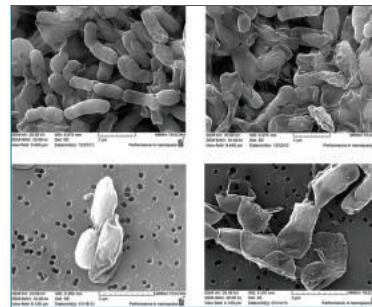
Applications



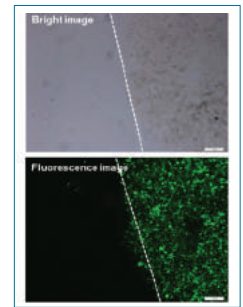
| Etching of Graphene



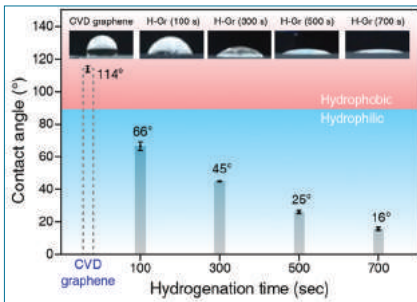
| Formation of Chemical Bonds by Plasma



| Sterilization



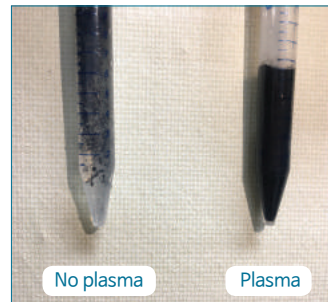
| Cell Culturing on Graphene



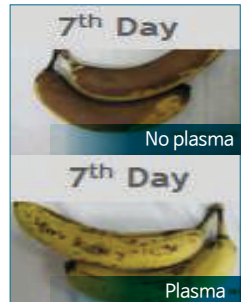
| Hydrophilicity of Graphene



| Anisotropic bacteria absorption



| Powder Treatment



| Plasma Treatment on Banana: Microorganism reduction



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